

High Refractive Index, High Accuracy Optical Resin

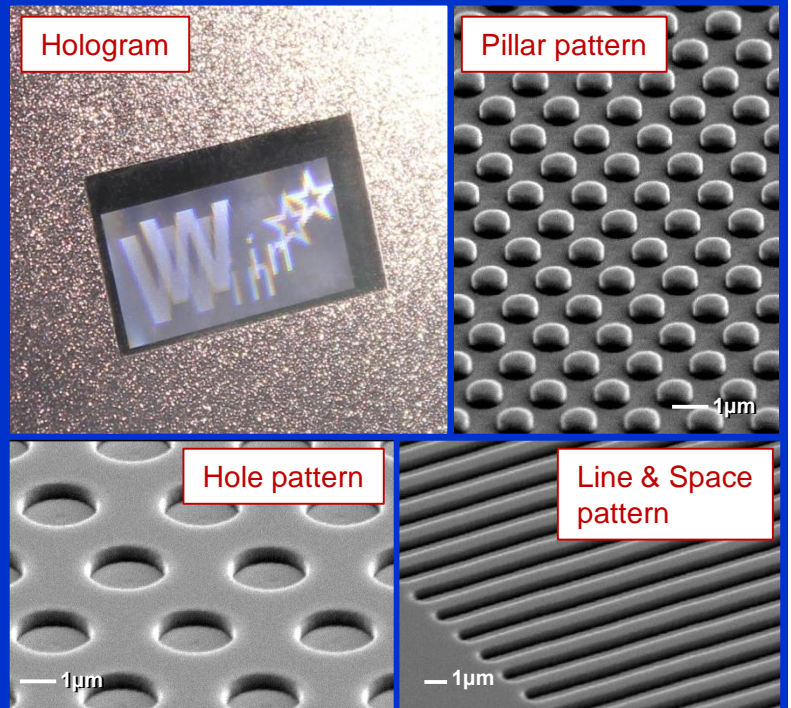
Optical Resin

Nano Imprint Lithography Resin

Nano imprint lithography is the next generation process technology.

The simple and low cost fabrication technology enables nano-scale patterns.

High RI, UV curable, nano imprint resin provides highly functional fine patterns.



High Accuracy

UV curing nano imprint lithography achieves high accuracy without high temperature processing.

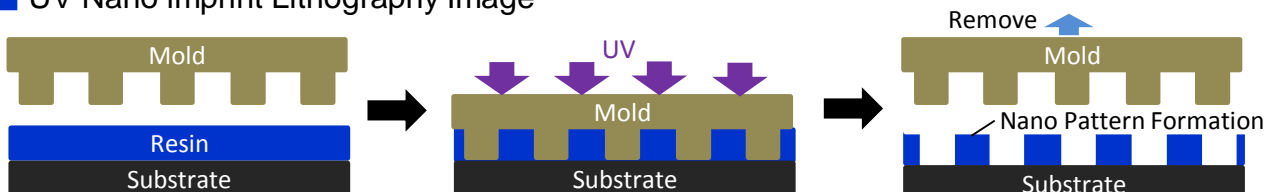
Characteristics of Resin can be Customized

By modifying the composition of UV resin, the characteristics can be customized.

High Transmittance

Although the refractive index of the material is high, the resin has a high transmittance above 400nm.

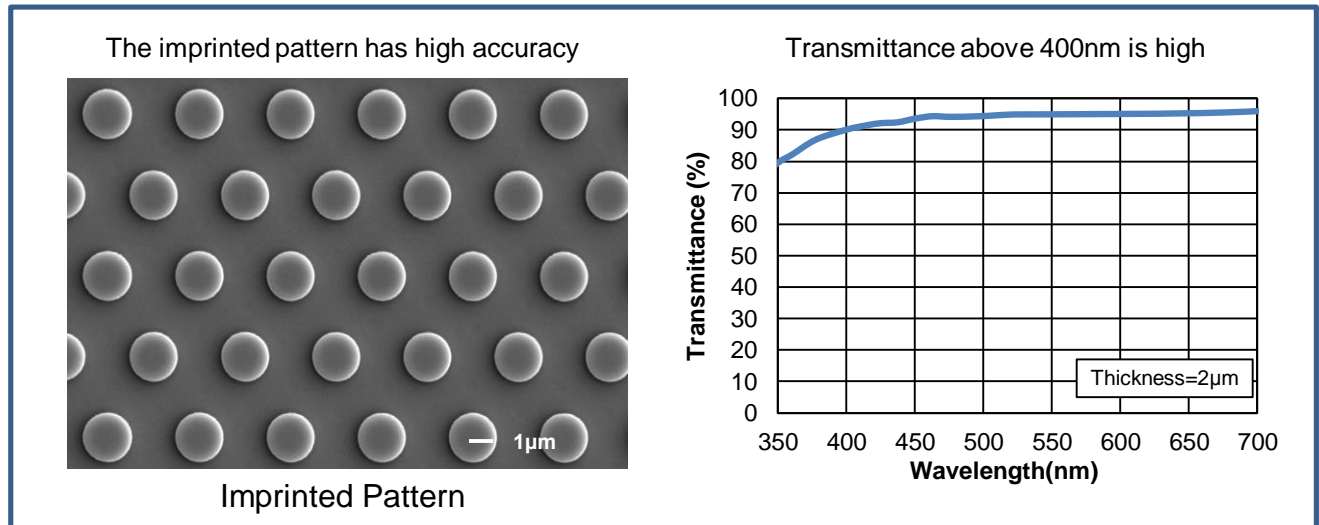
UV Nano imprint Lithography Image



■ Specifications (Preliminary)

Item		Test method : Condition	Unit	#18210
Before curing	Viscosity	E-type viscometer : 25°C	mPa · s	15
Curing condition	Pre Baking Conditions	-	-	115°C 1min
	UV Curing Conditions	-	-	100mW/cm ² 5min
After curing	Refractive Index	Prism coupler : 25°C	-	1.77 (403nm)
				1.72 (633nm)
				1.71 (848nm)
	Abbe's number	Abbe refractometer : 25°C	-	30
	Tg	Differential scanning calorimetry	°C	108
Transmittance	Spectrophotometer : Thickness=2μm	%	94 (450nm)	
			95 (540nm)	
			95 (630nm)	

■ Accuracy and Transmittance



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 ※ Please understand that all comments and data recorded herein may be subject to change without prior notification.
 ※ Numerical values listed are measured values. They are not performance guarantees.

For more information

<http://www.ntt-at.com/product/adhesive/>



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